

Notice of References Cited	Application/Control No. 10/632,825	Applicant(s)/Patent Under Reexamination LEE ET AL.	
	Examiner Evan Pert	Art Unit 2826	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
	E	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Lee et al., "Atomic Layer Deposition of Aluminum Thin films Using an Alternating Supply of Trimethylaluminum and a Hydrogen Plasma", 2002, Electrochemical and Solid-State Letters, 5 (10), C91-C93.
	V	Ohring, The Materials Science of Thin Films, 1992, Academic Press, Inc., , pages 339-340.
	W	Web article entitled "chemisorption and physisorption" retrieved on October 13, 2005 from "http://www.iupac.org/reports/2001/colloid_2001/manual_of_s_and_t/node16.html", 2 pages
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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